

IN THE ABSTRACT:

Please cancel the current abstract and insert the following. A marked-up copy showing the changes made to the abstract is attached hereto in Appendix A.

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g -- An exposure apparatus for illuminating a reticle with exposing light from an exposing light source via a light-source lens system, and projecting a pattern, which has been formed on the reticle, onto a wafer via a projection lens system, thereby exposing the wafer to the pattern. The apparatus includes vessels for hermetically sealing the light-source lens system and the projection lens system disposed on the optical path of the exposing light from the exposing light source to the reticle, a gas supply unit for supplying the vessels with a specific gas, a vacuum source for evacuating the interior of the vessels, a vacuum-pressure controller for exercising control to hold the internal pressure of the vessels constant, and an escape valve for reducing the differential pressure between the internal pressure of the vessels and atmospheric pressure to a value below a predetermined pressure. --

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IN THE SPECIFICATION:

Please amend the specification as follows:

Please substitute the paragraph beginning at page 1, line 21, and ending on page 2, line 12, with the following. A marked-up copy of this paragraph, showing the changes made thereto, is attached in Appendix A.